

From Physics to Daily Life

Micro-Fabricated Sensors

Cinzia Da Vià, The University of Manchester, UK



26/09/2014

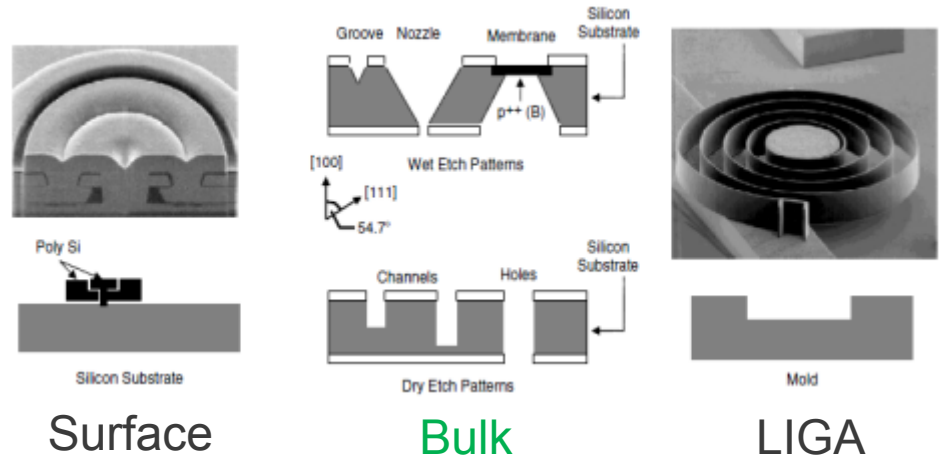
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Micro-Fabrication

In Micro-fabrication, used mainly for Micro-Electro Mechanical Systems (MEMS), the process is performed 3 dimensionally within the silicon volume.

Different processing types include:

- ❖ Surface: Structures are formed by deposition and etching of sacrificial and structural thin films
- ❖ Bulk, Volume: 3D structures formed by dry or wet etching of silicon substrates
- ❖ LIGA: 3D structures formed by mold fabrication followed by injection molding or electroplating



Applications:

- Everyday life (cars, portable devices..)
- Medical/Biology
- Space
- High Energy Physics
- ...

Industrial applications: sensors and actuators

Sensing Applications

Actuating Applications

Voice/
sound

Motion/
position

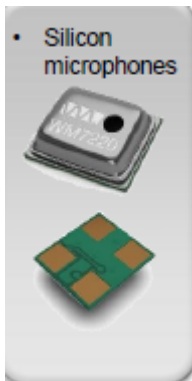
Pressure/
monitoring

Projecting
Receiving
light

RF
Related
functions

Managing
fluids

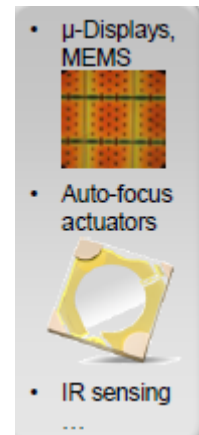
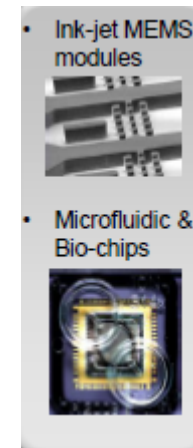
Emerging
MEMS



TPMS
Tire pressure monitoring system

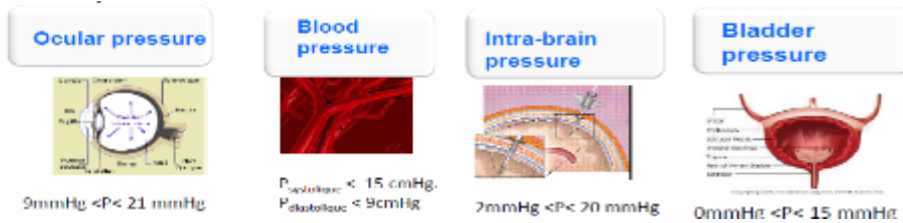


Surface
acoustic
wave

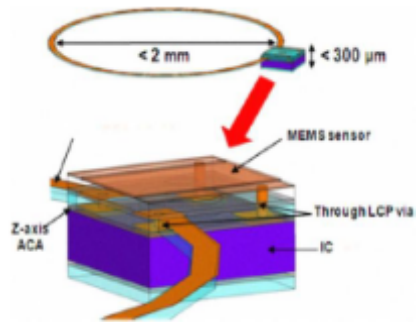


Applications in Bio-Medicine

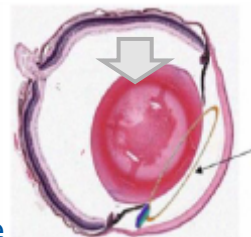
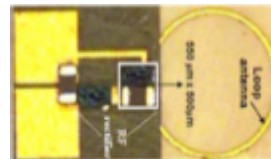
Pressure Sensing



Glaucoma diagnosis



D. Ha et al. IMS 2010

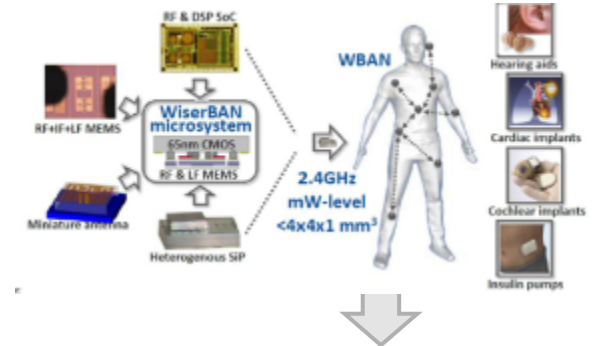


3D IC and MEMS stacking

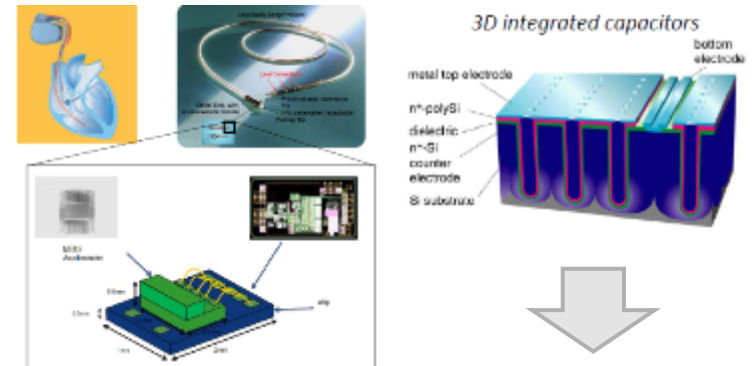
Inserted in a mouse's eye



Implantable Devices



Acceleration monitoring in pacemakers

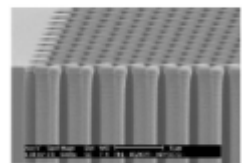


Energy Management
500 nF/mm
Using high k dielectrics

DRIE etched pores



DRIE etched pillars



Source: Roozeboom, Lamy et al., NXP, Power SOC 2008

Applications in HEP*: 3D sensors

*High Energy Physics

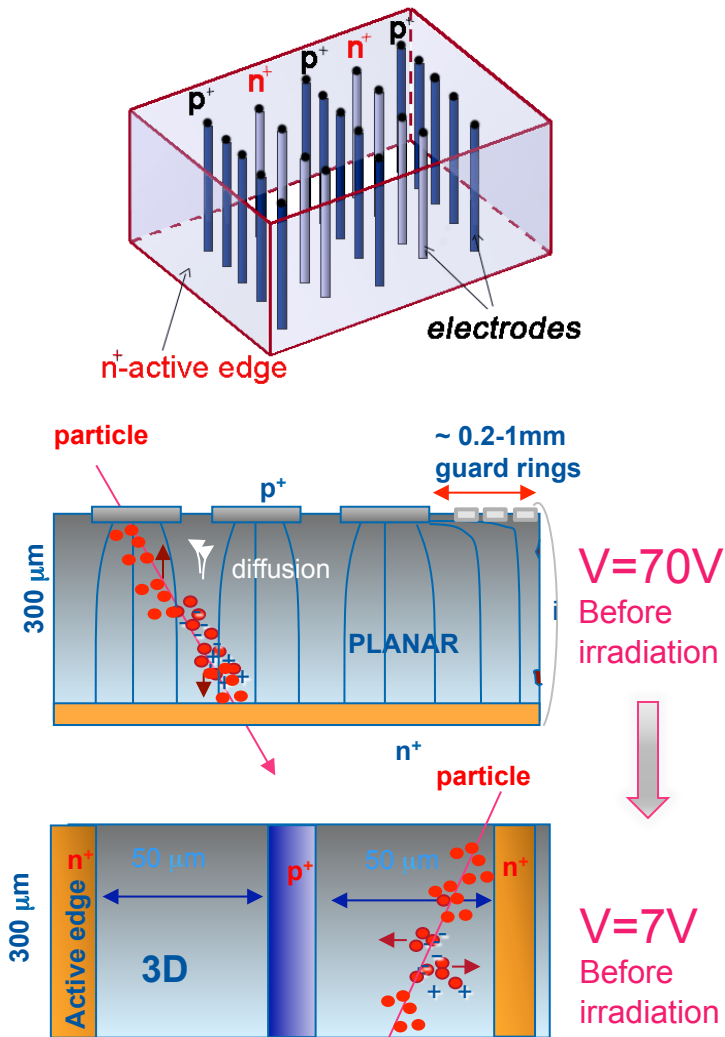
3D silicon detectors were proposed in 1995 by S. Parker, and active edges in 1997 by C. Kenney.

Combine traditional electronics processing and MEMS (Micro Electro Mechanical Systems) technology.

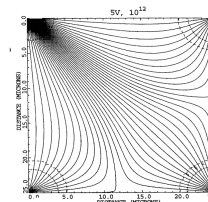
Electrodes are processed inside the detector bulk instead of being implanted on the Wafer's surface.

The edge is an electrode! Dead volume at the Edge < 5 microns!

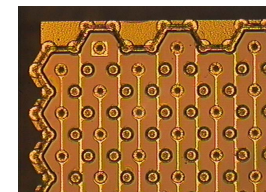
The electric field is parallel to wafer's surface: and smaller inter-electrode spacing: low bias voltage, low power, reduced charge sharing and high speed – for the same wafer thickness



Drift lines parallel to the surface



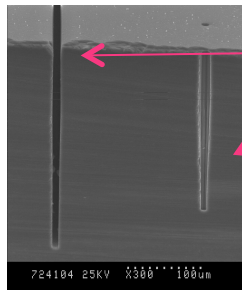
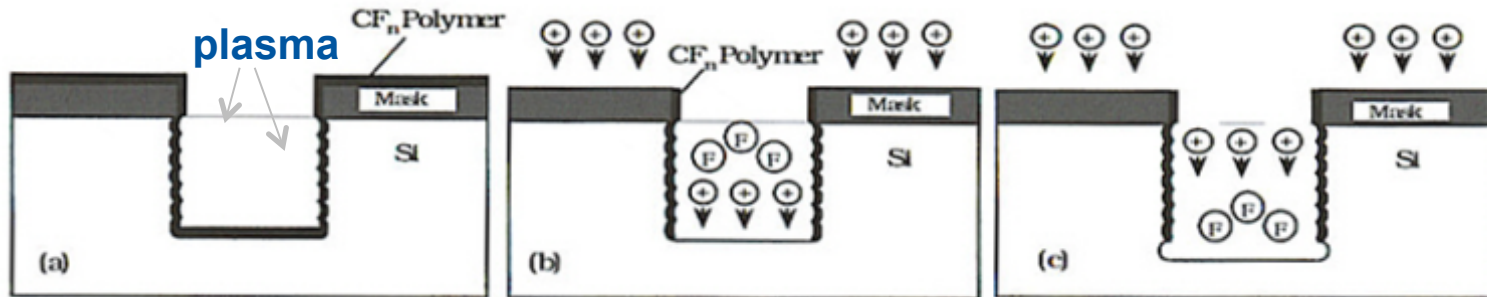
MEDICI simulation of a 3D structure



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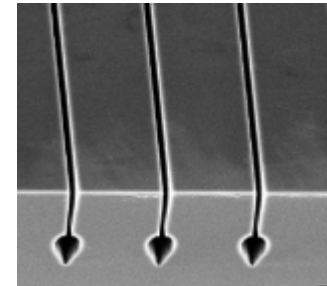
Deep Reactive Ion Etching

Bosch Process

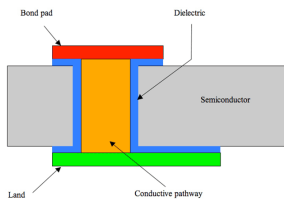


Deep pores and trenches

micro-channels

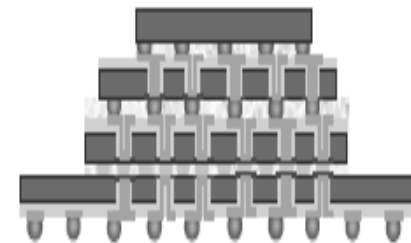


Interconnectivity Using TSV



1. Drawing showing the key features of a through silicon via (TSV). A TSV can be defined as "A structure that provides an electrical pathway through the thickness of a semiconductor (silicon) die between a bond pad on the front face and a land on the rear face. The pathway, bond pads and lands are all electrically isolated from the semiconductor." Drawing not to scale. Source: Tsvista.

Vertically integrated electronics

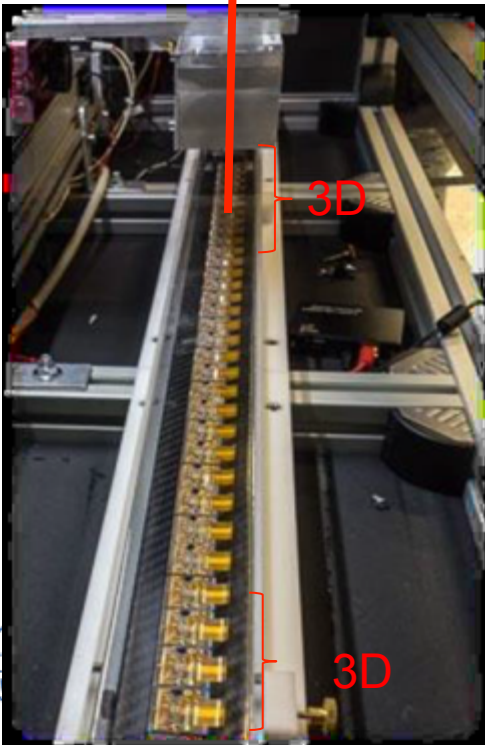
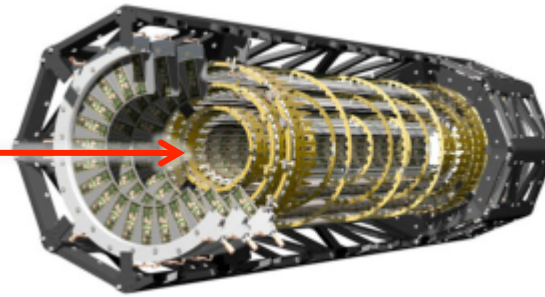
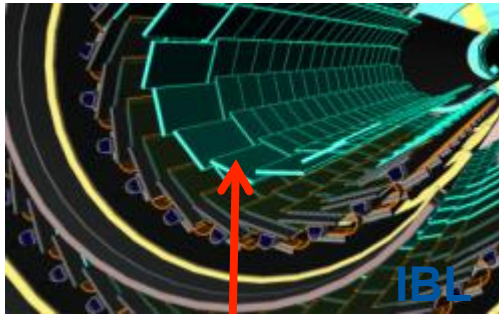


3D sensors are now in the core of ATLAS



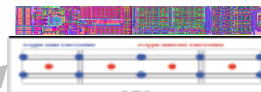
3DATLAS R&D
Collaboration

NIMA 694 (2012) 321–330
2012 JINST 7 P11010.



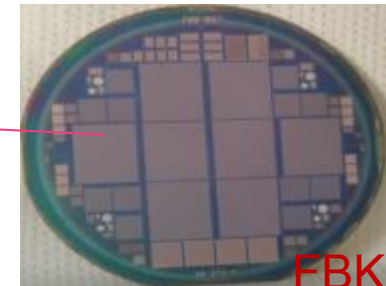
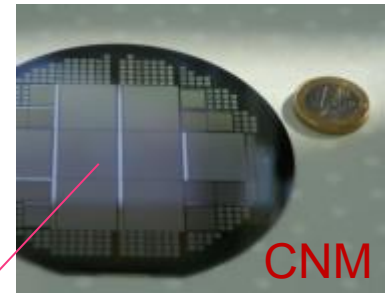
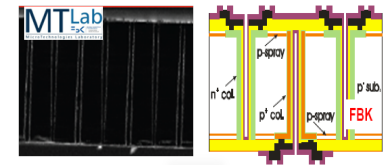
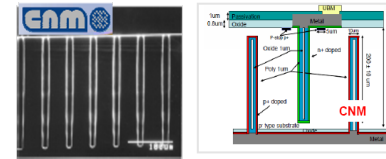
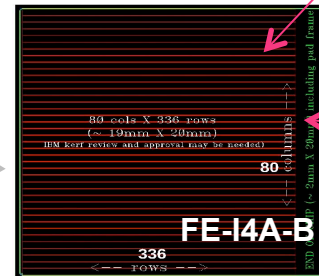
3D sensors just being installed in the first LHC detector upgrade in the ATLAS –Insertable B-Layer (IBL)

>300 sensors fabricated to cover 25% IBL



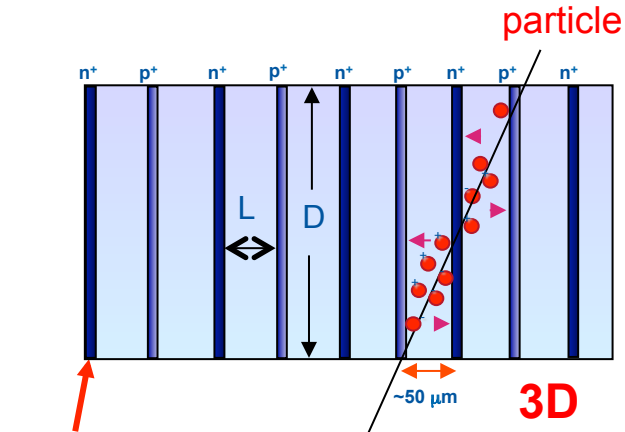
250 x 50 μm^2

FE-I4 = 2x2cm²
336 x 80
250x50 μm^2 , 26880
pixels

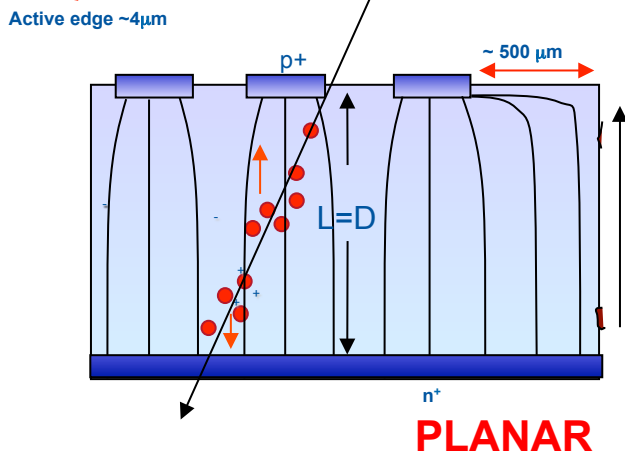
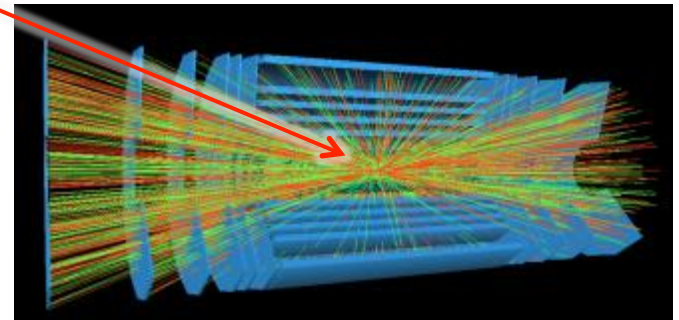


3D sensors and radiation hardness

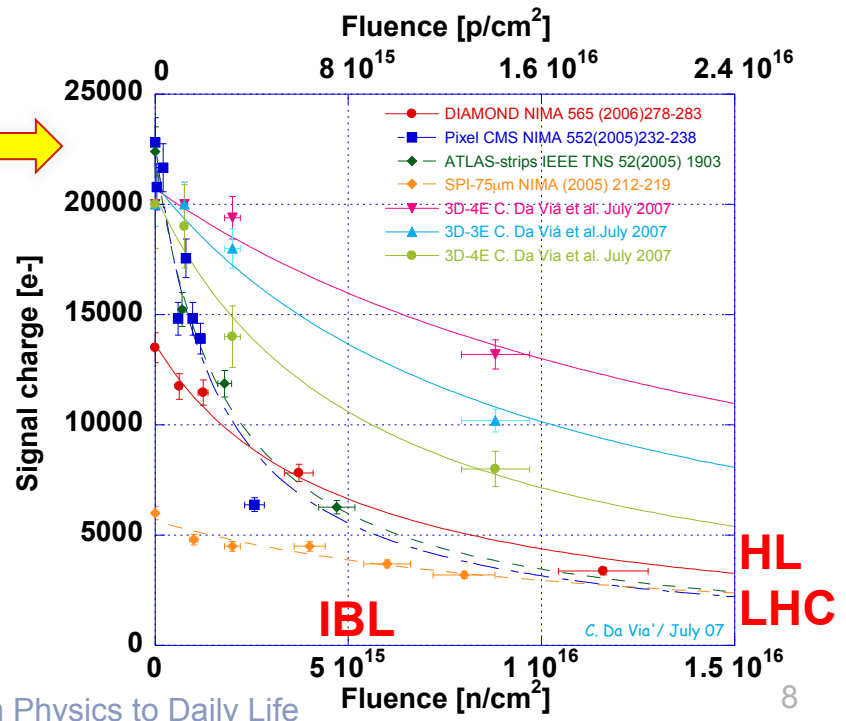
In the LHC experiments Vertex Detectors will be exposed to the highest radiation level



- Shorter drift distance
- Stronger e-field
- Generated signal decoupled from drift distance



3D 4E (54um)
 3D 3E (71um)
 3D 2E (105um)
 Diamond
 Thick Si
 Thin Si

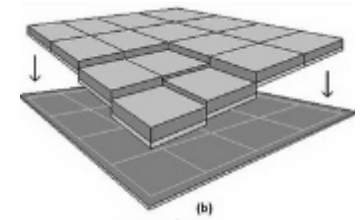


Fluence in 1MeV equivalent neutrons per cm²

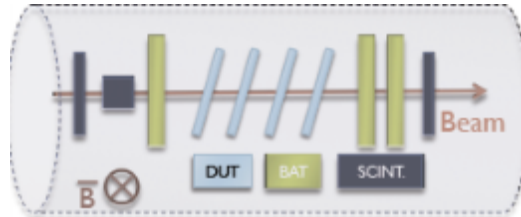
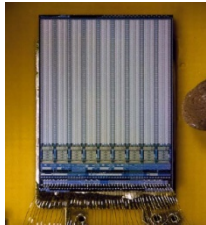


3D sensors with active edges

Fully sensitive volumes, large area imagers

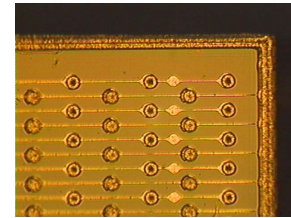


Test beam setup at CERN



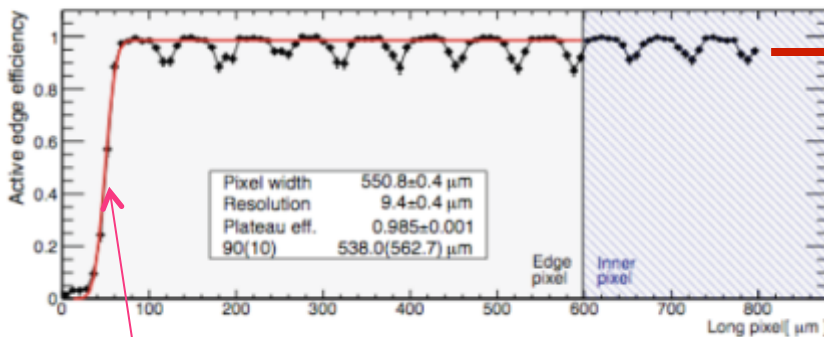
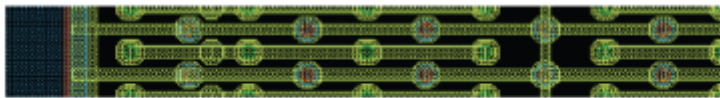
Test beam with x-ray micro beam At Berkeley USA

2 μm , 14 KeV X-rays)

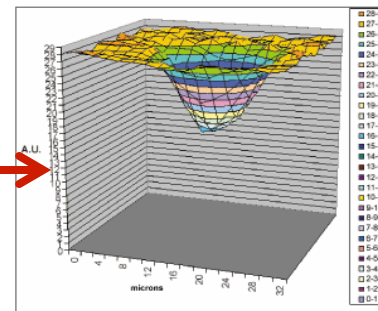


Active edge details

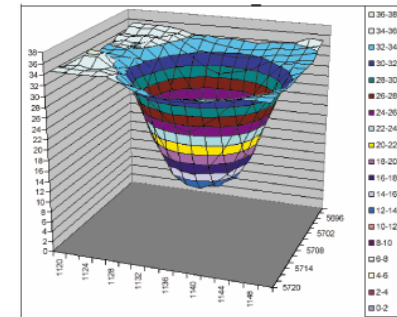
120 GeV pions at CERN SpS



Active Edge = $6 \pm 9.8 \mu\text{m}$



N – Electrode
Signal Reduction 43%



P – Electrode
Signal Reduction 66%

Differences between N and P:

Grain size of poly, Diameter, Diffusion rate, Trapping, Doping

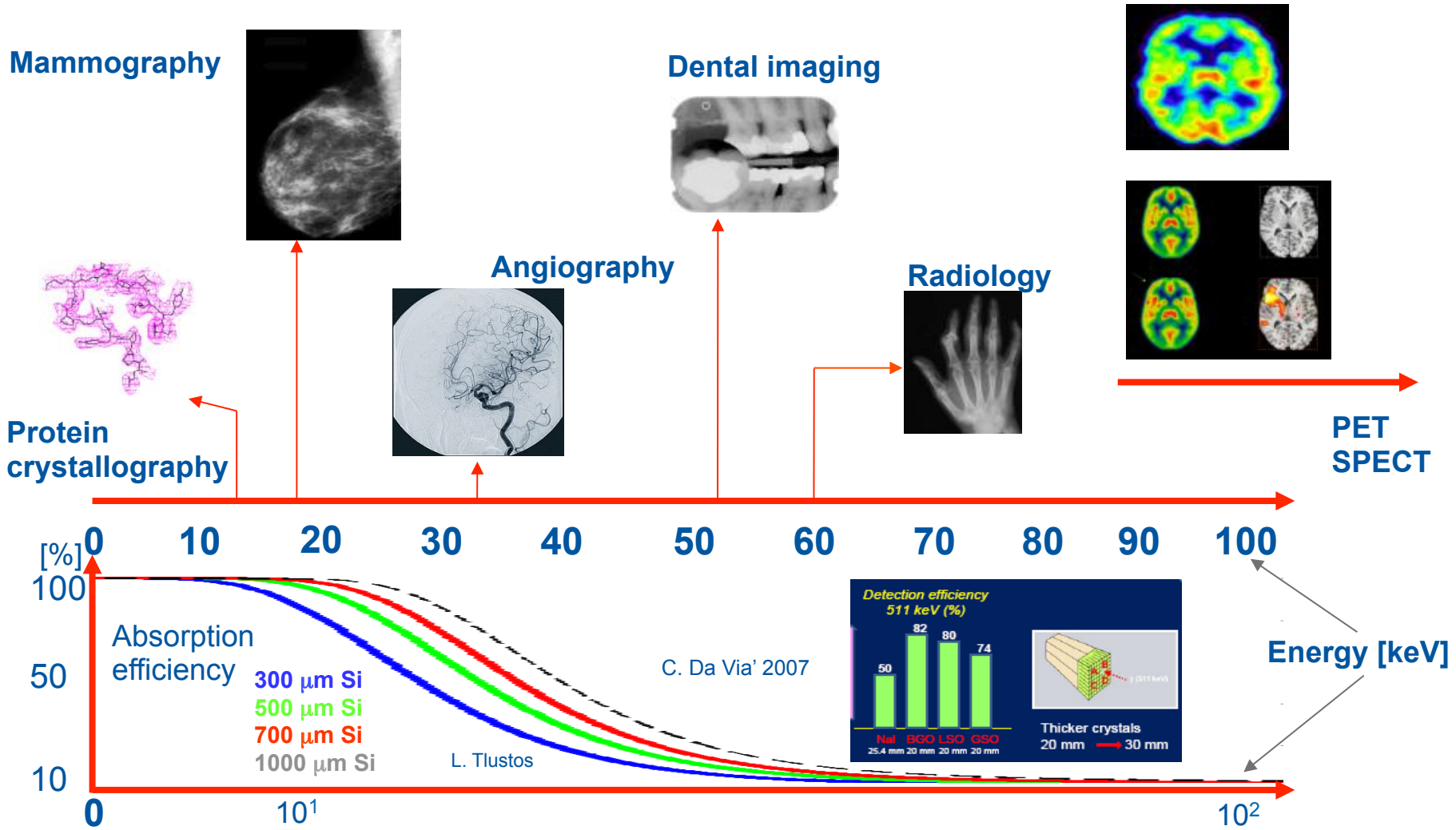
Electrodes response is not zero if filled with poly-silicon

J. Hasi PhD Thesis



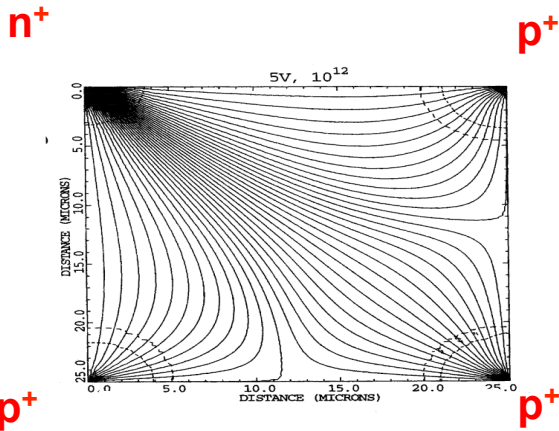
P. Hansson et al. Nuclear Instruments and Methods in Physics Research A 628 (2011) 216–220

X-ray energies in medicine and biology



Charge sharing and increased thickness

Medical Imaging, X-ray Spectroscopy

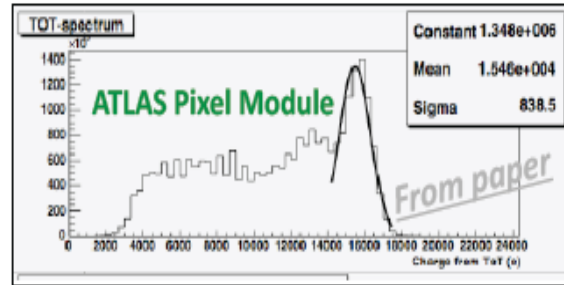


3D Electric field

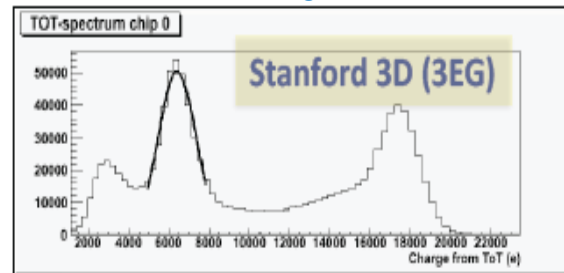
Reduced charge sharing allows better energy resolution at lower energies

Stacked geometry allows thicker substrates and better detection efficiency at higher X-ray energies with preserved performance

planar



3D

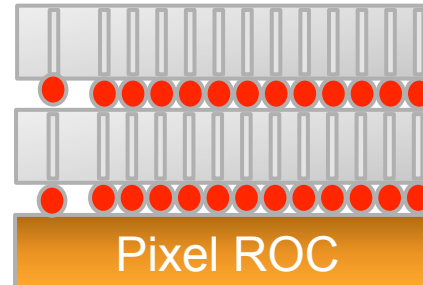


Measurements by A. La Rosa CERN Now UniGeneva (CH)

²⁴¹Am

Type	Energy	Percentage
Alpha (α)	5.485 MeV	84.5 %
Alpha (α)	5.443 MeV	13.0 %
Beta (β)	52 keV	Unknown
Gamma (γ)	59.5 keV	35.9 %
Gamma (γ)	26.3 keV	2.4 %
Gamma (γ)	13.9 keV	42 %

Measurements Performed using the ATLAS FE-I3 Readout chip and the TurboDAQ system (developed in Bonn)



Micro-dosimetry

for Cancer Therapy, Space Radiation Monitoring

Microdosimetry measures the stochastic energy deposition events at cellular level

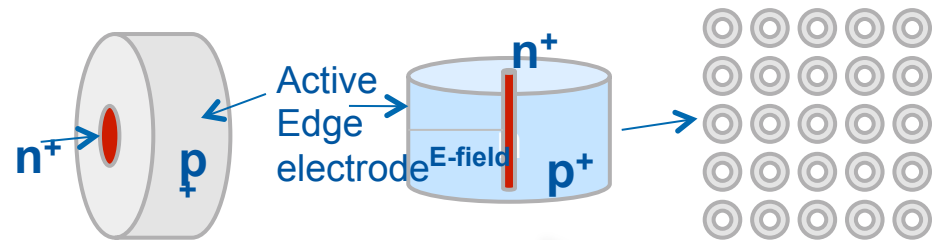
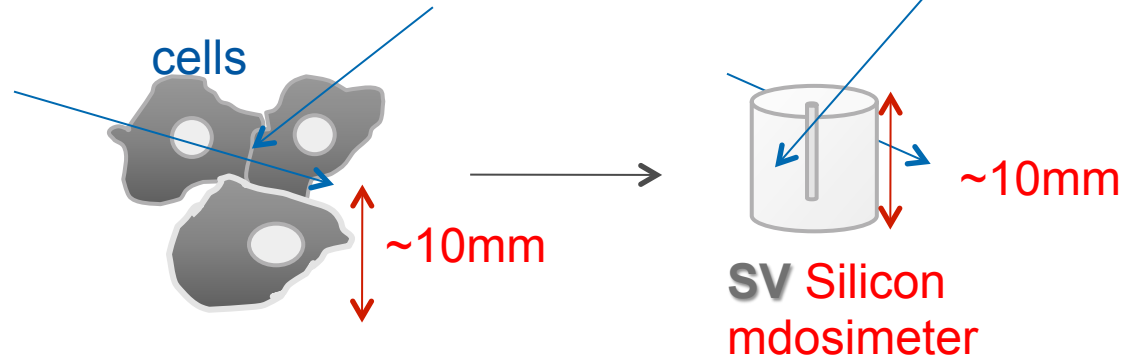
Radio-Biological Effectiveness (RBE) depends on linear energy transfer (LET or Lineal Energy) which is different for different radiation type. **Average chord length $\langle l \rangle$ is independent on radiation direction**

❖ **Mixed Field** detection in a small sized array of cell-like elements of well defined Sensitive volume **SV** is required to precisely determine RBE

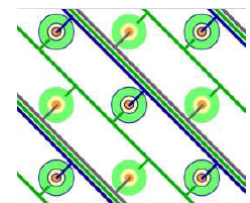
❖ Silicon Dose Equivalent can be determined From the lineal Energy Spectra and the tissue equivalent dose D_{TE} . Quality factors **Q** are determined Experimentally.

$$D_{Si} = D_{TE} S_{Si}/S_{TE}$$

$$\text{Dose equivalent } H = Q D_{Si}$$



3D sensors with central n^+ electrode surrounded by p^+ trench define cellular size sensitive volume

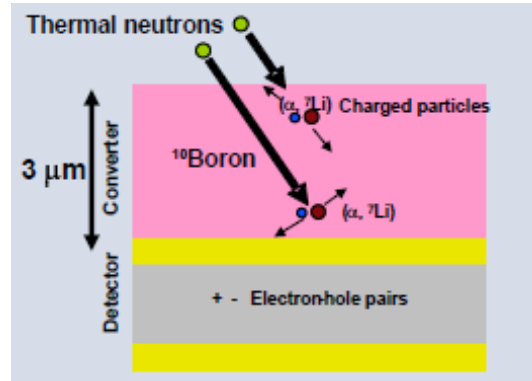


High Efficiency Neutron Detection

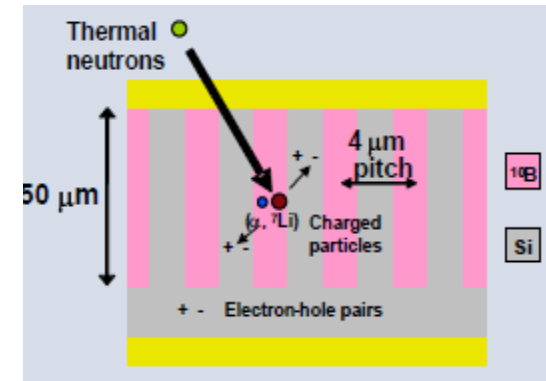
Neutron capture therapy, diffraction



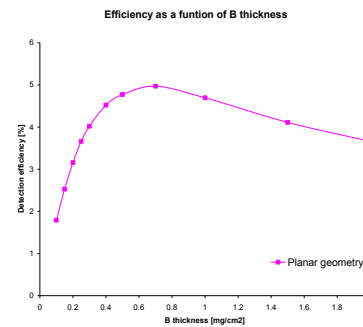
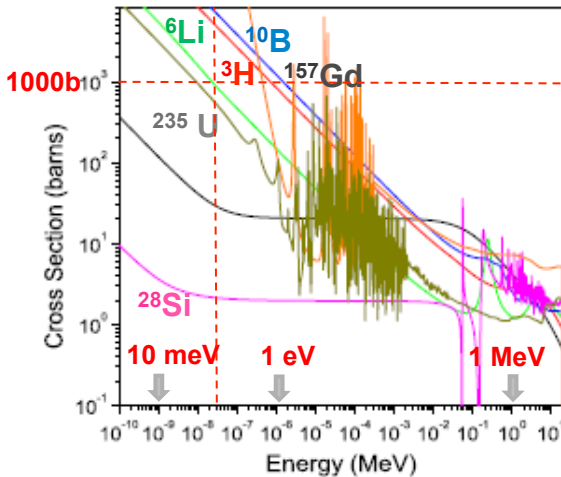
- Silicon is not sensitive to neutrons but is a well established radiation detector
- Need neutron reactive converter materials usually deposited on the surface thin films or different geometries
- With reference to ^{10}B converter:
 - 90% capture in 43 μm
 - Range of reaction products 2-5 μm



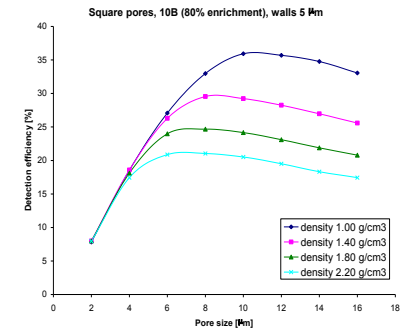
Planar geometry



Micro-fabricated Squares



Amorphous ^{10}B , enrichment 80%
Efficiency < 5%



Efficiency up to 36%

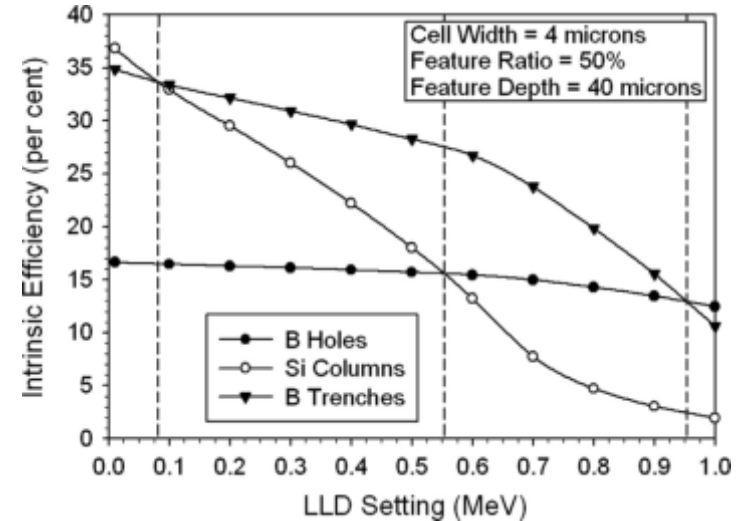
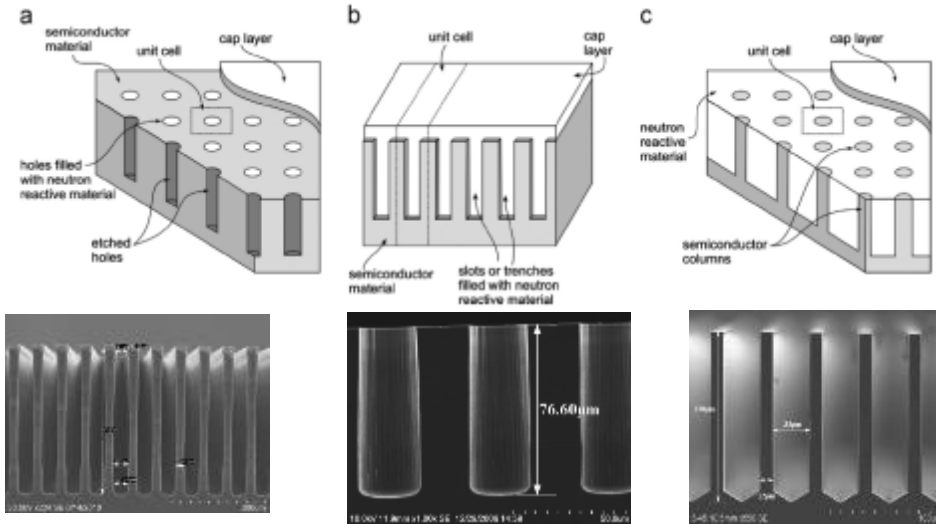


Neutron cross sections of some common n-reactive materials



Micro-structured Semiconductor Neutron Detectors (MSND)

D. McGregor et al., J. Crystal Growth 379 (2013) 99



- Extended interaction surface, and higher probability for reaction products to enter the semiconductor
- Different shapes and geometries

Comparison of efficiencies as a function of feature size, as measured by its cell fraction, for hole, trench and column designs with unit cell dimensions of 4 μm and feature depths of 40 μm. ^{10}B is the back fill material and the LLD was set for 300keV

Conclusions

- Micro Fabricated Sensors developed for High Energy Physics have found applications in other fields like medicine and biology
- Future developments include astronomy, environmental monitoring and space applications